

ABSTRACT OF THE DISCLOSURE

An evaporation method and an apparatus thereof are disclosed. The evaporation apparatus comprises a rotator, a heater and a source supplying device. The rotator, which is disposed above the central portion of the substrate, can rotate the substrate. An
5 evaporation source is disposed on the heater, and the evaporation region is a circular region. The heater and the source supplying device are disposed below the substrate, wherein the source supplying device provides the evaporation source on the heater along a supply direction. In order to prevent the location of the evaporation source shifts along the supply direction from affecting the uniformity of deposited film, a
10 circular trace is defined and the heater is disposed below the circular trace so that the supplying direction is parallel to the tangential direction of the circular trace.